

L Number	Hits	Search Text	DB	Time stamp
1	98	((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:19
2	3	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:20
3	1	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and neon	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:24
4	2	((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:25
5	21	430/313.cor. and 430/328.cxr. not (etch\$3 with chamber)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:28
6	17	((((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate))) and etch\$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:30
7	3	((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:31
8	15	(430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:32
9	12	((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) same (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:32
10	2	((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:33
11	26	((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:33

12	98	((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:34
13	646	(430/328.ccls. not 430/313.cor.) not (((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((430/328.ccls. not 430/313.cor.) and ((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:36
14	3	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:37
15	1	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and neon	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:37
16	0	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:38
17	135	((ultraviolet or uv) with (Ne)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:38
18	7	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:39

19	89	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:39
20	4	430/313.cor. and 430/328.cxr. and (etch\$3 with chamber)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:40
21	5	250/504R-504H.ccls. and (neon or Ne) with (ultraviolet or uv)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:41
22	19	430/328.ccls. and (uv or ultraviolet or ultra adj violet) same (temperature or \$4"degree") same plasma	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:42
23	156	430/328.ccls. and (uv or ultraviolet or ultra adj violet) same (temperature or \$4"degree") not plasma	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:45
24	43	430/313.ccls. and (uv or ultraviolet or ultra adj violet) same (\$4"degree") same plasma not 430/328.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 11:03
25	374	(resist or photoresist) same (uv or ultraviolet or ultra adj violet) same (\$4"degree") same plasma	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 11:04
26	25	250/504R-504H.ccls. and plasma and (uv or ultraviolet or ultra adj violet) same (\$4"degree")	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 11:05